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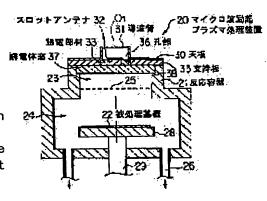
(54) DEVICE AND METHOD FOR PROCESSING MICRO WAVE EXCITING PLASMA

(57)Abstract:

PROBLEM TO BE SOLVED: To be able to suppress

products from peeling.

SOLUTION: This device 20 is so constituted of a ceiling board 30 which is provided at a terminal side of a guide wave tube and to which micro wave is propagated, as the micro wave to radiate from a micro wave introducing port formed on the ceiling board 30 toward the inside of a responding vessel 21 and as medium gas to turn to plastic radiation for a board 22 to be processed to plasmic radiation. In this case the device is provided with a dielectric window 37 which encloses an upper terminal port of the responding vessel 21 in airtight, transmits the micro wave and guides a processed of the micro wave at the inside, and with a dielectric member 33 which is provided corresponding to a slot antenna 32 at the spot closer to the ceiling board side 30 than the dielectric window 37, introduces the micro wave radiated by the slot antenna 32, and regulates the processed to the H surface direction.



LEGAL STATUS

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